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(12) **United States Design Patent**
Kuwabara et al.

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(54) **ELECTRODE PLATE FOR A PLASMA
PROCESSING APPARATUS**

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(73) Assignee: **Tokyo Electron Limited**, Tokyo (JP)

(**) Term: **14 Years**

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(30) **Foreign Application Priority Data**

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(51) **LOC (10) Cl.** **13-03**

(52) **U.S. Cl.**
USPC **D13/182**

(58) **Field of Classification Search**
USPC D13/182; D15/144, 144.1, 199;
118/715; 414/935-941, 147, 217;
156/345.53; 279/128; 361/230, 233,
361/234; 204/193, 194, 279, 280, 281, 282,
204/283, 284, 285, 286.1, 297.01; 205/118,
205/123; 200/293, 302.1, 308

See application file for complete search history.

(56) **References Cited**

U.S. PATENT DOCUMENTS

D363,464 S * 10/1995 Fukasawa D13/182
D404,370 S * 1/1999 Kimura D13/182
D404,372 S * 1/1999 Ishii D13/182
D411,516 S 6/1999 Imafuku et al.
6,818,097 B2 * 11/2004 Yamaguchi et al. 156/345.47
D546,784 S * 7/2007 Hayashi D13/182
D548,705 S * 8/2007 Hayashi D13/182
D556,704 S * 12/2007 Nakamura et al. D13/182
D557,226 S * 12/2007 Uchino et al. D13/182
7,479,304 B2 * 1/2009 Sun et al. 427/289
D606,952 S * 12/2009 Lee et al. D13/182

D609,652 S * 2/2010 Nagasaka et al. D13/182
D609,655 S * 2/2010 Sugimoto D13/182
D614,593 S * 4/2010 Lee et al. D13/182
D648,289 S * 11/2011 Mayer et al. D13/182
D654,883 S * 2/2012 Honma et al. D13/182

(Continued)

FOREIGN PATENT DOCUMENTS

KR 30-0335385 10/2003

OTHER PUBLICATIONS

Taiwanese Office Action, Application No. 101301746, dated Oct. 24, 2012.

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(57) **CLAIM**

The ornamental design for an electrode plate for a plasma processing apparatus, as shown and described.

DESCRIPTION

FIG. 1 is a front view of an electrode plate for a plasma processing apparatus showing our new design, the rear view being identical;

FIG. 2 is a right side view thereof, the left side view being identical;

FIG. 3 is a top plan view thereof;

FIG. 4 is a bottom plan view thereof;

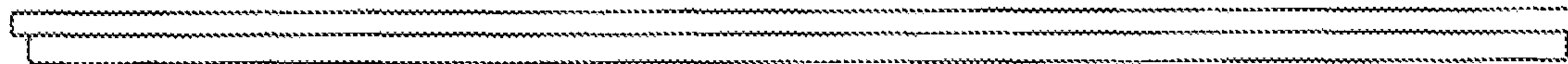
FIG. 5 is an enlarged view of a portion of the electrode plate for a plasma processing apparatus of FIG. 1 taken along line 1-1 and line 2-2 of FIG. 3;

FIG. 6 is an enlarged cross sectional view thereof, taken along line 3-3 of FIG. 5; and,

FIG. 7 is a perspective view of the electrode plate for a plasma processing apparatus of FIG. 1.

The features shown only in broken lines depict environmental subject matter only and form no part of the claimed design.

1 Claim, 7 Drawing Sheets



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(56)

References Cited

U.S. PATENT DOCUMENTS

D655,257 S *	3/2012	Honma et al.	D13/182	
D655,259 S *	3/2012	Honma et al.	D13/182	
2003/0066484 A1 *	4/2003	Morikage et al.	118/723 E	
D654,884 S *	2/2012	Honma et al.	D13/182	* cited by examiner

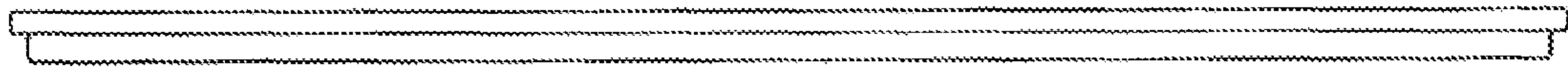


Figure 1

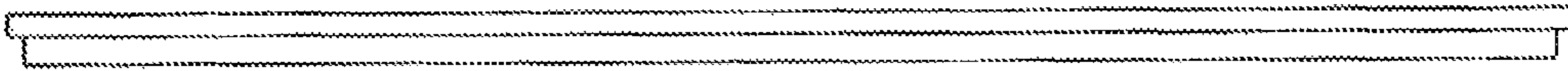


Figure 2

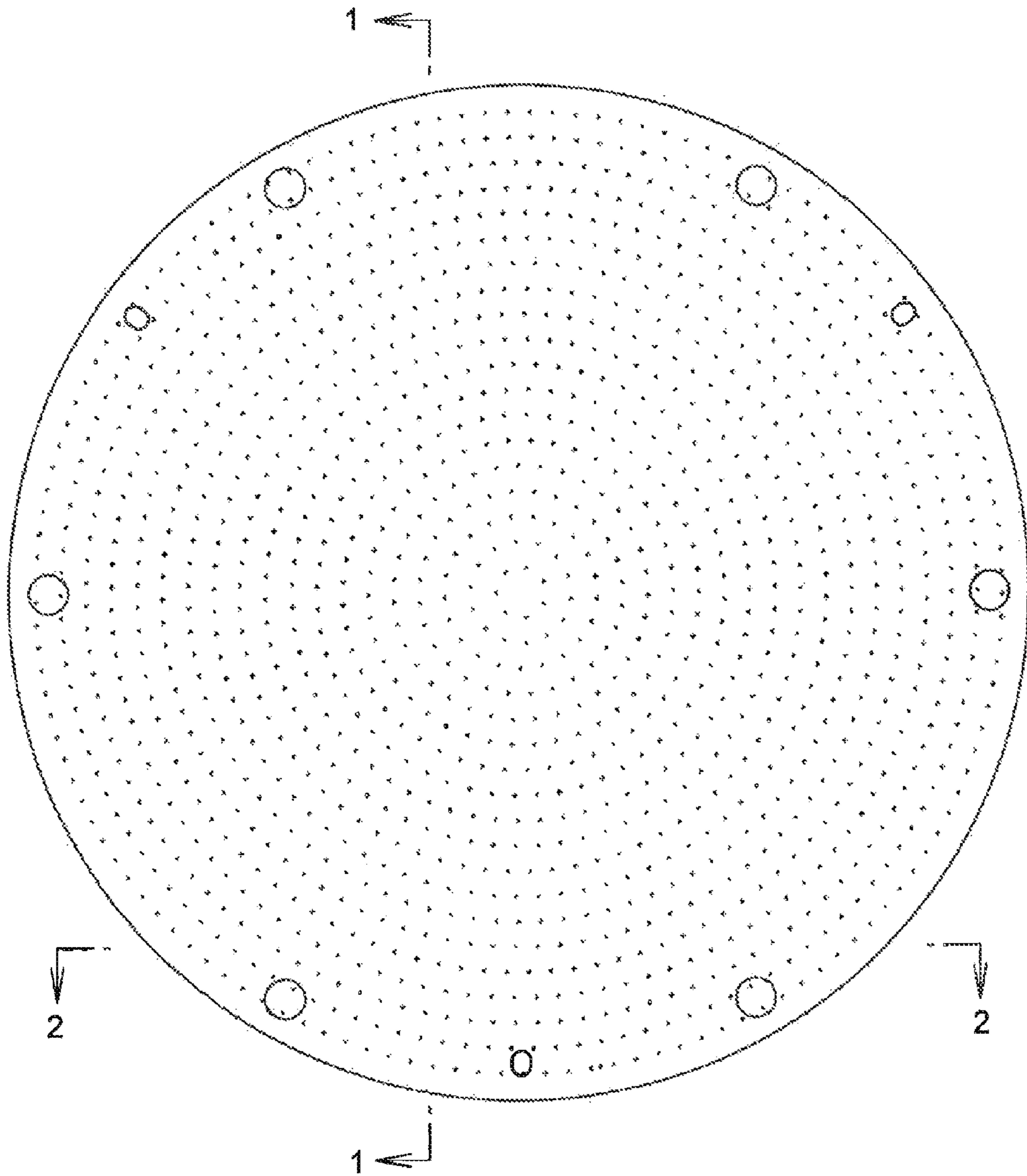


Figure 3

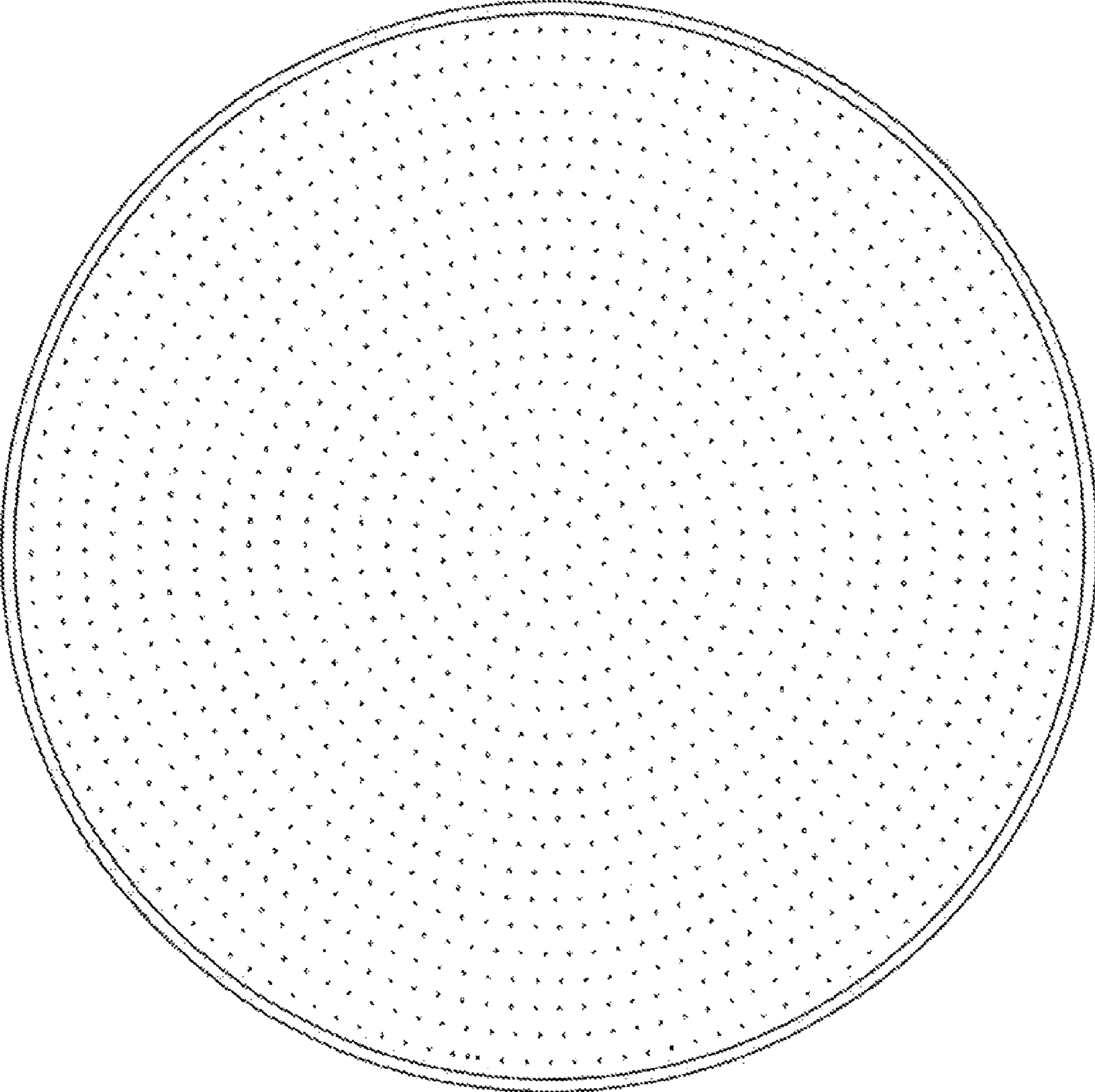


Figure 4

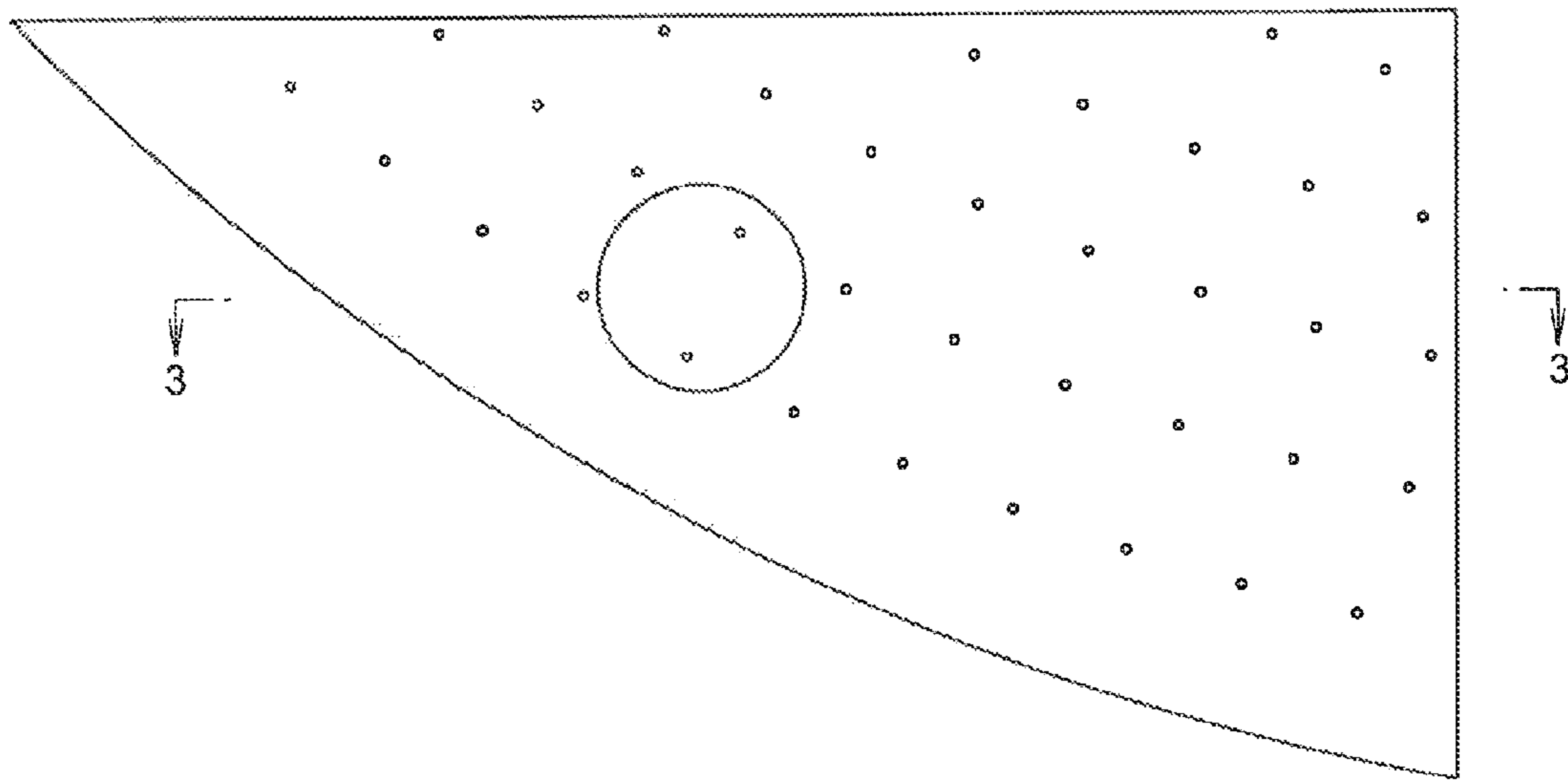


Figure 5

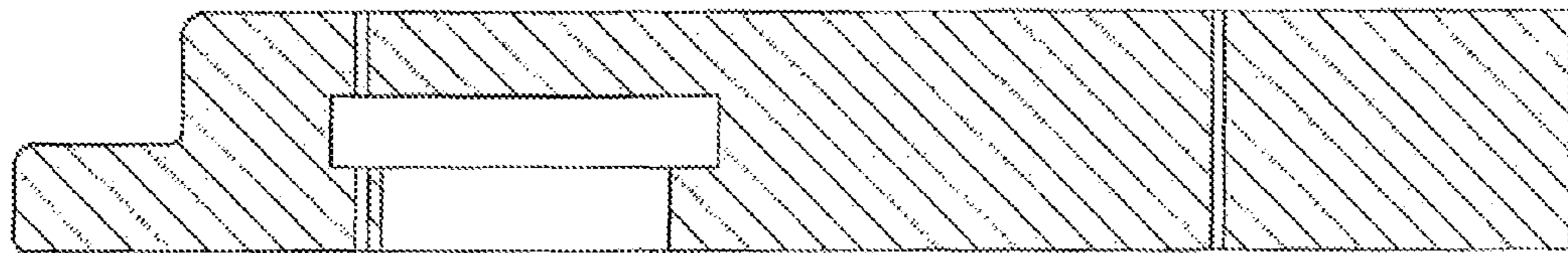


Figure 6

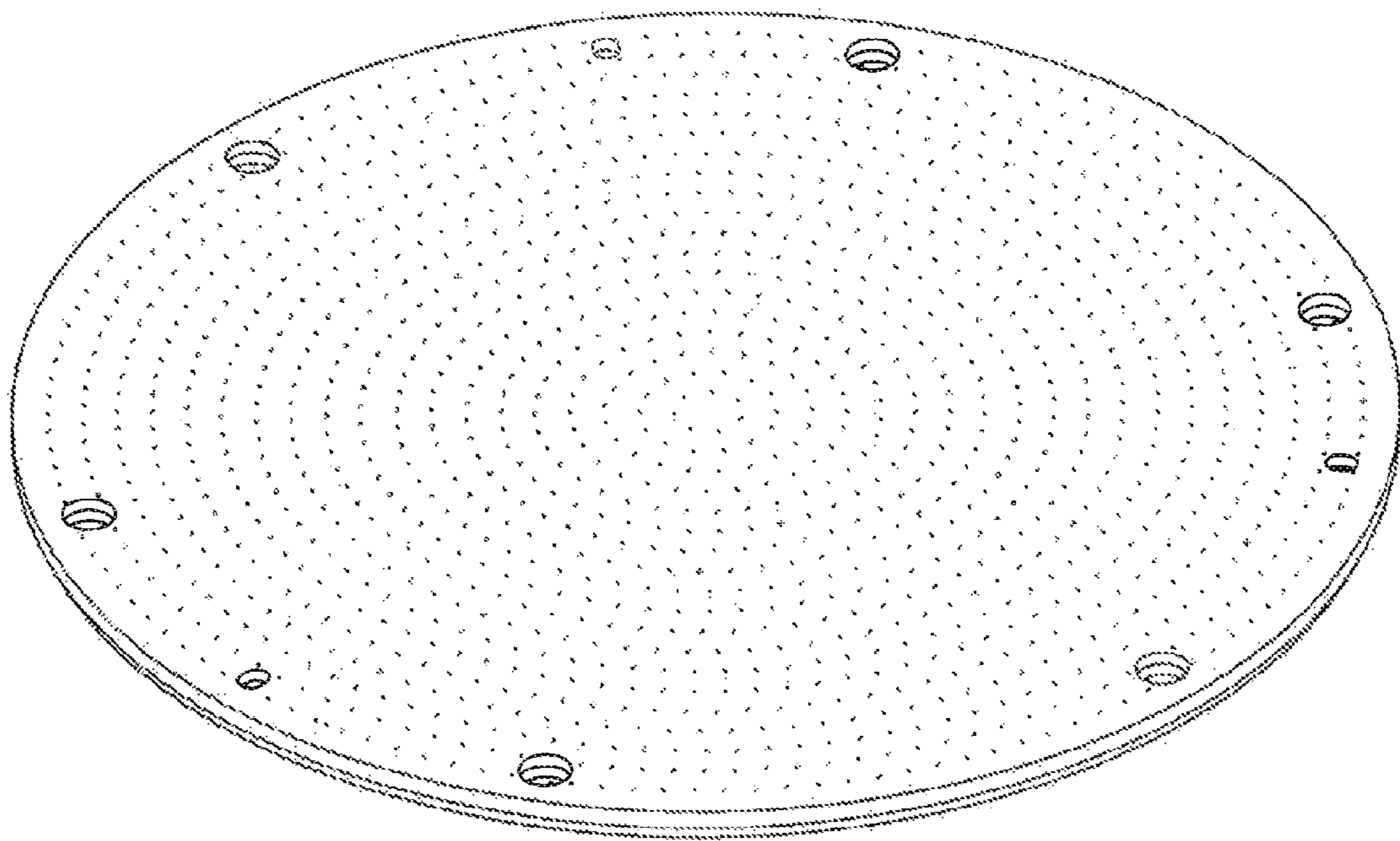


Figure 7